

IN THE CLAIMS:

Please amend Claim 3 by rewriting this claim as follows:

a² -- 3. (Amended) Gas for excimer laser used for an excimer laser device which oscillates pulsed laser by exciting gas for excimer laser sealed in a chamber, wherein the gas for excimer laser contains an effective amount of an additive xenon gas for reducing burst and spiking phenomena caused in an excimer laser output in the burst operation. --

Please add the following new claims:

a³ -- 5. An excimer laser device having a mechanism for sealing gas for excimer laser in a chamber and carrying out pulse oscillation in the chamber to excite the gas for excimer laser so to oscillate pulsed laser, which carries out burst operation by repeating a continuous pulse oscillation operation period and a pulse oscillation stopping period, comprising:

xenon gas supplying means for supplying xenon gas as an additive into the gas for excimer laser in the chamber; and

control means for controlling an amount of the xenon gas supplied to the chamber so that a concentration of the xenon gas in the chamber becomes a predetermined concentration by which burst and spiking phenomena caused in an excimer laser output in the burst operation can be lowered. --

-- 6. An excimer laser device according to claim 5, comprising:
concentration sensing means for detecting the concentration of the xenon gas
in the chamber, wherein

the control means controls the amount of the xenon gas supplied to the
chamber based on the concentration of the xenon gas detected by the
concentration sensing means. --

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-- 7. Gas for excimer laser used for an excimer laser device which has a
mechanism for oscillating pulsed laser by exciting gas for excimer laser sealed
in a chamber, and which carries out burst operation by repeating a continuous
pulse oscillation operation period and a pulse oscillation stopping period,
wherein the gas for excimer laser contains a predetermined concentration of
xenon gas that can lower burst and spiking phenomena caused in an excimer
laser output in the burst operation. --

-- 8. An excimer laser device according to claim 7, wherein the gas for
excimer laser contains 200 ppm or below of the xenon gas. --

REMARKS

In the foregoing amendments, Claim 3 was amended to define that the
gas for the excimer laser contains an effective amount of xenon gas for
reducing burst and spiking phenomena caused in an excimer laser output in